

**AMENDMENTS TO THE CLAIMS**

1. (Original) A process of forming a thin film on a large size glass substrate by spraying comprising the steps of:

preparing, as the large size glass substrate, plate glass produced by a float bath process in which molten glass is poured into an Sn bath and gradually hardened;

applying a coating solution containing an alcohol as a solvent onto the bottom surface of the plate glass, which is formed by bringing the molten glass into contact with the Sn bath, by spraying; and

forming a metal oxide thin film.

2. (Original) A process of forming a thin film on a large size glass substrate by spraying comprising the steps of:

applying a coating solution containing an alcohol as a solvent and water of from 5% by mass to 15% by mass onto the large size glass substrate by spraying; and

forming a metal oxide thin film.

3. (Original) A process of forming a thin film on a large size glass substrate by spraying comprising the steps of:

preparing, as the large size glass substrate, plate glass produced by a float bath process in which molten glass is poured into an Sn bath and gradually hardened;

applying a coating solution containing an alcohol as a solvent and water of from 5% by mass to 15% by mass onto the bottom surface of the plate glass, which is formed by bringing the molten glass into contact with the Sn bath, by spraying; and  
forming a metal oxide thin film.

4. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 3~~ claim 1, wherein among the water contained in the coating solution, the water of from 5% by mass to 10% by mass with respect to the total coating solution is added after an alcohol solution of a metal oxide raw material is prepared.

5. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 4~~ claim 1, wherein the metal oxide thin film comprises titanium oxide and/or silicon oxide.

6. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 4~~ claim 1, wherein the coating solution comprises titanium alkoxide and/or silicon alkoxide.

7. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 6~~ claim 1, wherein the coating solution comprises titanium oxide fine particles and/or silicon oxide fine particles.

8. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 7~~ claim 1, wherein the coating solution is applied by spraying onto the glass substrate while keeping the surface temperature of the glass substrate at 35°C or lower.

9. (Currently Amended) The process of forming a thin film on a glass substrate according to ~~any one of claims 1 to 8~~ claim 1, wherein the coating solution is applied by spraying onto the glass substrate while keeping the surface temperature of the glass substrate at 35°C or lower and then the surface temperature of the glass substrate is raised to 100°C to 300°C.

10. (Currently Amended) A glass substrate coated with a thin film, wherein the substrate is produced by the process according to ~~any one of claims 1 to 9~~ claim 1.

11. (New) The process of forming a thin film on a glass substrate according to claim 2, wherein among the water contained in the coating solution, the water of from 5% by mass to 10% by mass with respect to the total coating solution is added after an alcohol solution of a metal oxide raw material is prepared.

12. (New) The process of forming a thin film on a glass substrate according to claim 3, wherein among the water contained in the coating solution, the water of from 5% by mass to 10% by mass with respect to the total coating solution is added after an alcohol solution of a metal oxide raw material is prepared.

13. (New) The process of forming a thin film on a glass substrate according to claim 2, wherein the metal oxide thin film comprises titanium oxide and/or silicon oxide.

14. (New) The process of forming a thin film on a glass substrate according to claim 3, wherein the metal oxide thin film comprises titanium oxide and/or silicon oxide.

15. (New) The process of forming a thin film on a glass substrate according to claim 4, wherein the metal oxide thin film comprises titanium oxide and/or silicon oxide.

16. (New) The process of forming a thin film on a glass substrate according to claim 2, wherein the coating solution comprises titanium alkoxide and/or silicon alkoxide.

17. (New) The process of forming a thin film on a glass substrate according to claim 3, wherein the coating solution comprises titanium alkoxide and/or silicon alkoxide.

18. (New) The process of forming a thin film on a glass substrate according to claim 4, wherein the coating solution comprises titanium alkoxide and/or silicon alkoxide.

19. (New) The process of forming a thin film on a glass substrate according to claim 2, wherein the coating solution comprises titanium oxide fine particles and/or silicon oxide fine particles.

20. (New) The process of forming a thin film on a glass substrate according to claim 3, wherein the coating solution comprises titanium oxide fine particles and/or silicon oxide fine particles.